

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION  
METHOD OF PHOTOMASK, AND  
FABRICATION METHOD OF  
SEMICONDUCTOR INTEGRATED  
CIRCUIT



) Group Art Unit: 1756

) Examiner: S. Mohamedulla

**AMENDMENT UNDER 37 C.F.R. § 1.111**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

This amendment responds to the Office Action dated May 24, 2000 (Paper No. 4).

Concurrently filed with this Amendment are abstracts of the references cited in the

Information Disclosure Statement. Please amend the above-noted application as follows:

**IN THE CLAIMS:**

Please amend claims 2-15 and 20 and add new claims 27 and 28 as follows:

Claim 2, line 3 change "said" to --a--;

line 6, change "flat" to --planarized--.

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3. (Amended) A photomask according to claim 2, wherein an end section of said phase shift pattern that is contacted to said transparent substrate has a sloped shape that gradually decreases, the sloped shape formed by chemical and mechanical polishing.